



We have many low-cost solutions that can help keep your fab competitive.

- Contamination removal & control
- Light source management
- Tool & component monitoring

**SemiPhotoMet**

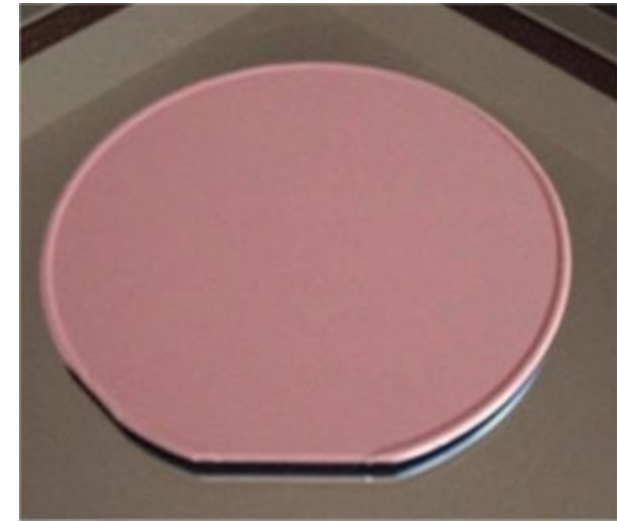
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# Chuck Cleaning Wafer



.....Helping keep your tools clean,  
wafers moving, and profits high.....

**SemiPhotoMet**

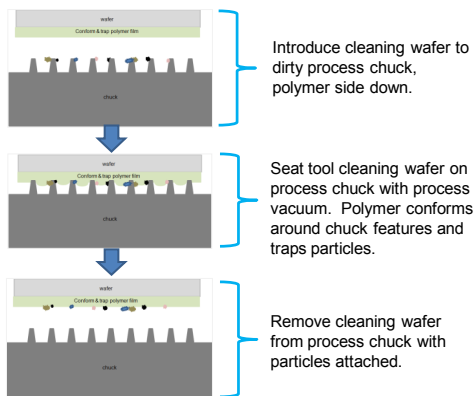
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# Chuck Cleaning Wafer\*

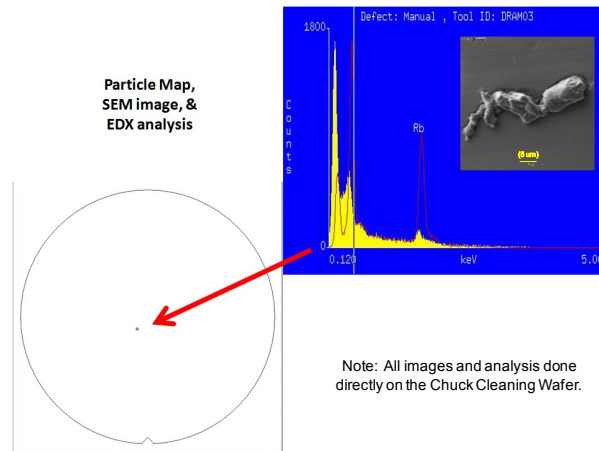
Proprietary silicon-based polymer film attached to a Si or GaS wafer that can be loaded and unloaded in process tools like any other wafer, manually or automated. Picks up and removes particulate material attached to tool chuck and robot transfer arm without taking tool out of production.

- No out-gassing
- No transference to process tool
- Operates to 300 deg C
- Removes contaminates from process
- Enables quick analysis of particles
- 4" - 12" wafer sizes available
- Edge bead or exclusion available
- Customized for your application
- Demonstrated success in:
  - Steppers/scanners
  - Tracks
  - Etchers
  - PVD
  - Metrology

## How the Wafer Cleans



- Removes "hot spots" on stepper/scanner chucks. 85% - 95% effective.
- Reduce photo re-work up to 50%.
- Removes particles that cause vacuum failures in etchers and PVD tools.
- Increases product yield and reliability.
- Many customers get 100 uses before end-of-life.
- Particles, including *photo resist*, collected on the CCW can be quickly inspected and analyzed directly with standard wafer inspection tools.



\* Product of International Test Solutions

Manufacturing tools are collection points for particulates as particles travel around the fab on the backs of wafers. Cleaning tool chucks is an effective method of reducing yield-limiting particulates in the fab, and reducing tool downtime.

Customers often find that this product can clear their particulate problem without having to take their tools out of production for multiple hour cleanings.

Using this product won't cause an expensive chuck to be damaged due to "over-stoning" or other manual cleaning techniques.

*Try this product before taking your tool out of production for cleaning, or when you need a quick method of finding the source of the particles in your process.*

*It will keep your process cleaner, yields higher, and maintenance time & cost less.*

*No other product in the market can match the performance and cost of this product.*

**SemiPhotoMet**